INFORMATION DISCLOSURE CITATION IN AN APPLICATION (PTO-1449)	ATTY. DOCKET NO. 008066 USA/ MTCG/PCTRL	SERIAL NO. 10/809,908
	APPLICANT Susie Xiuru YANG et al.	
	FILING DATE March 26, 2004	GROUP 2812

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U.S. PATENT DOCUMENTS

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EXAMINER *(signed)*	DATE CONSIDERED 11/14/05

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.